

Duy
Jan 28/2

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Gopinath et al.

Application No.: 10/016,017

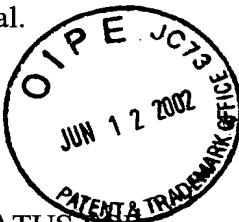
Filed: December 12, 2001

Title: METHOD AND APPARATUS FOR
INTRODUCTION OF SOLID PRECURSORS
AND REACTANTS INTO A SUPERCRITICAL
FLUID REACTOR

Attorney Docket No.:
NOVLP030/NVLS-000497

Examiner: Not yet assigned

Group: 2812



RECEIVED
JUN 17 2002
1C 2800 MAIL ROOM

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as First Class Mail to: Commissioner for Patents, Washington, DC 20231 on May 31, 2002.

Signed: *Tara Hayden*

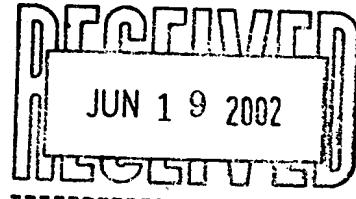
Tara Hayden

**INFORMATION DISCLOSURE STATEMENT
37 CFR §§1.56 AND 1.97(b)**

Commissioner for Patents
Washington, DC 20231

Dear Sir:

The references listed in the attached PTO Form 1449, copies of which are attached, may be material to examination of the above-identified patent application. Applicants submit these references in compliance with their duty of disclosure pursuant to 37 CFR §§1.56 and 1.97. The Examiner is requested to make these references of official record in this application.



This Information Disclosure Statement is not to be construed as a representation that a search has been made, that additional information material to the examination of this application does not exist, or that these references indeed constitute prior art.

This Information Disclosure Statement is: (i) filed within three (3) months of the filing date of the above-referenced application, (ii) believed to be filed before the mailing date of a first Office Action on the merits, or (iii) believed to be filed before the mailing of a first Office Action after the filing of a Request for Continued Examination under §1.114. Accordingly, it is believed that no fees are due in connection with the filing of this Information Disclosure

Form 1449 (Modified) Information Disclosure Statement By Applicant (Use Several Sheets if Necessary)	Atty Docket No. NOVLP030/NVLS-000497 Applicant: Gopinath et al. Filing Date December 12, 2001	Application No.: 10/016,017 Group 2812
--	--	---

U.S. Patent Documents

RECEIVED
JUN 17 2002
TC 2800 MATT ROON

Foreign Patent or Published Foreign Patent Application

Other Documents

Examiner Initial	No.	Author, Title, Date, Place (e.g. Journal) of Publication
	A	Biberger et al., "High Pressure Processing Chamber for Semiconductor Substrate", Pub. No. US 2002/0046707 A1, Pub. Date: April 25, 2002, Appl. No.: 09/912,844, Filed: July 24, 2001, pp. 1-19.
Examiner		Date Considered

Examiner: Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



Creation date: 10-29-2003

Indexing Officer: ICHARLES - IRENE CHARLES

Team: OIPEBackFileIndexing

Dossier: 10016017

Legal Date: 10-29-2003

No.	Doccode	Number of pages
1	ECBOX	1

Total number of pages: 1

Remarks:

Order of re-scan issued on